

Fig. 1

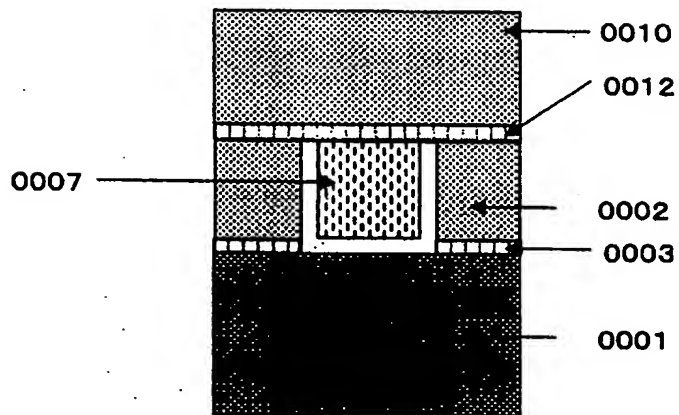
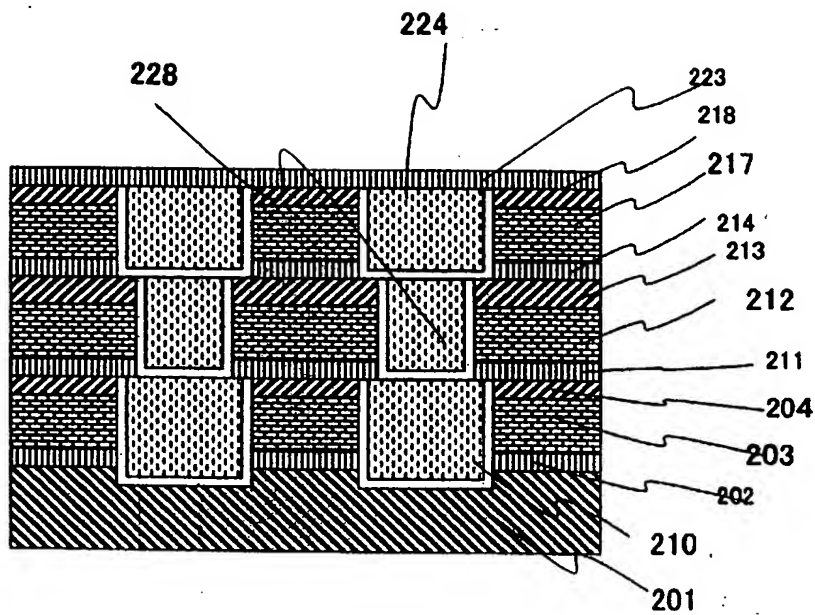


Fig. 2



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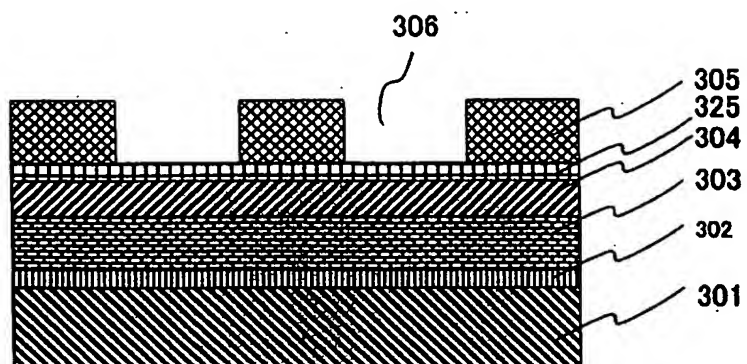


Fig. 3(a)

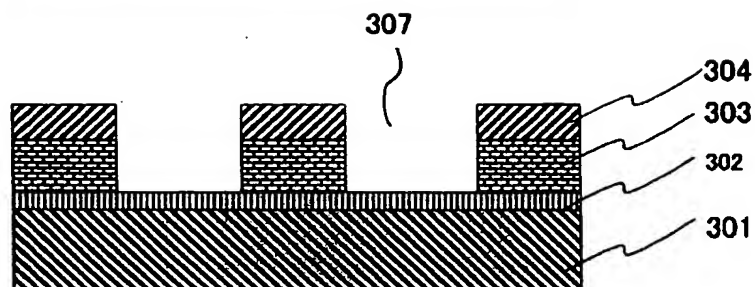


Fig. 3(b)

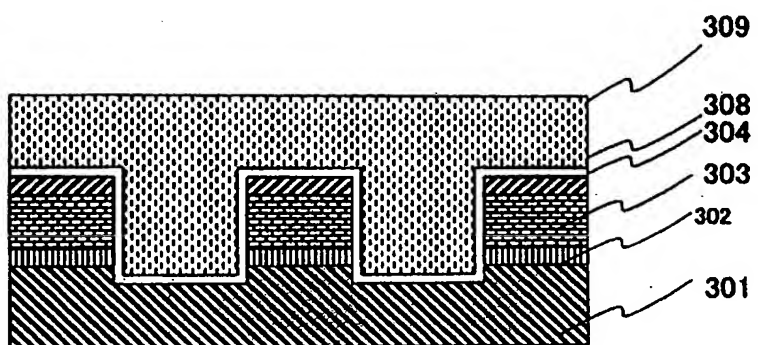


Fig. 3(c)

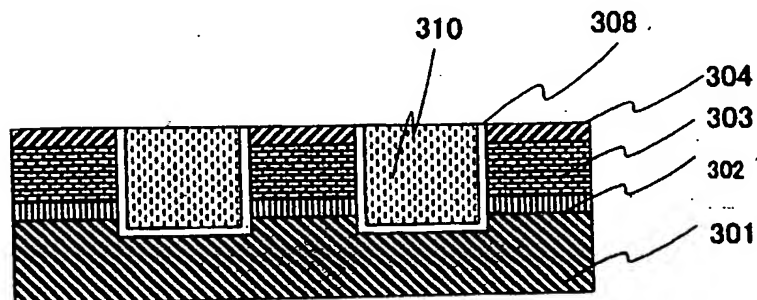


Fig. 3(d)

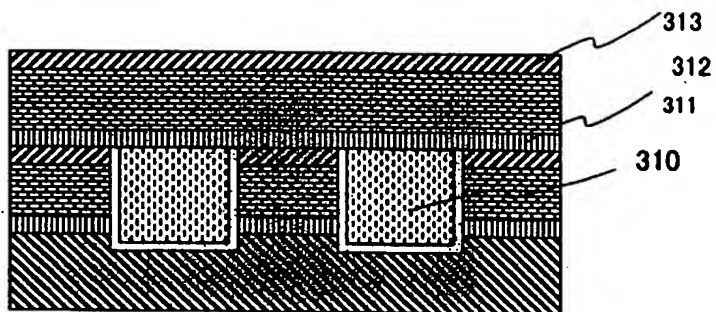


Fig. 4(a)

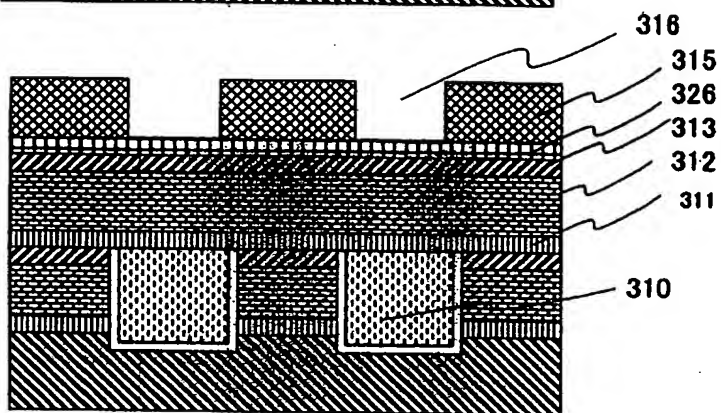


Fig. 4(b)

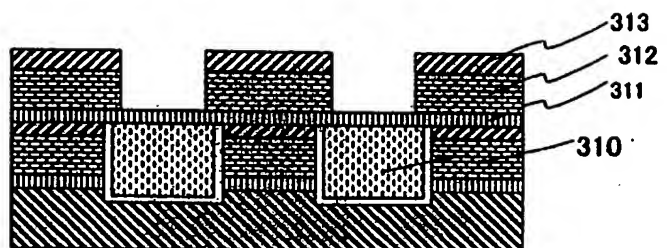


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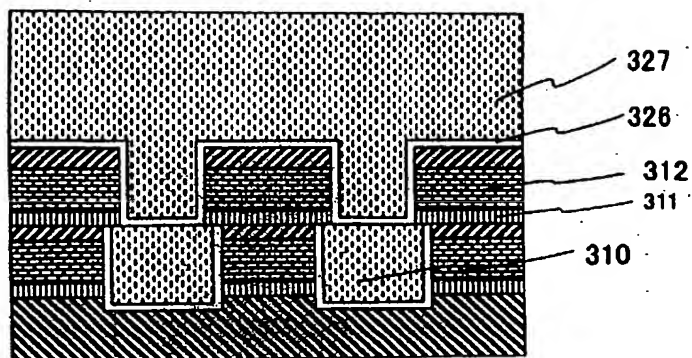


Fig. 4(d)

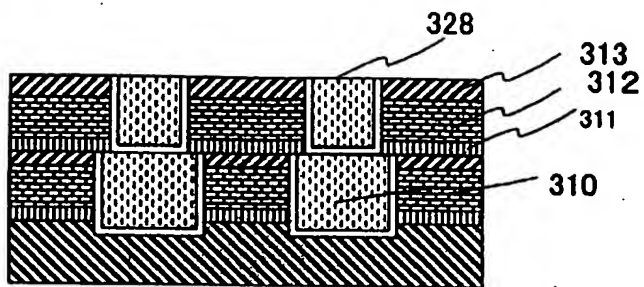


Fig. 5(a)

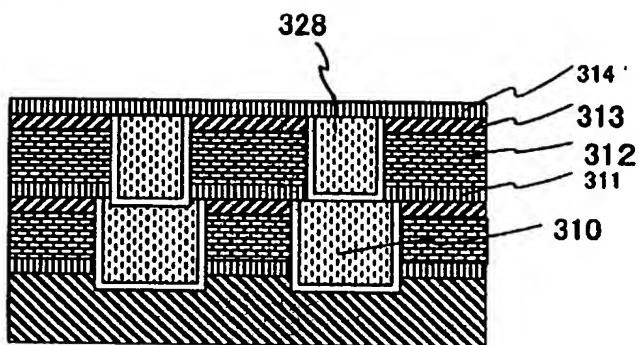


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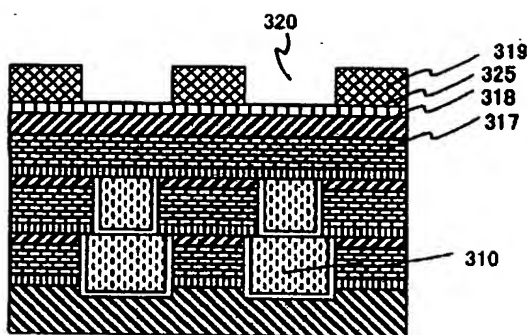


Fig. 5(c)

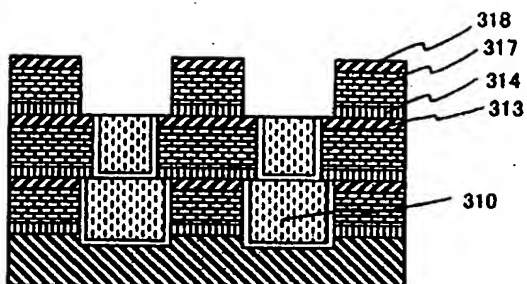


Fig. 5(d)

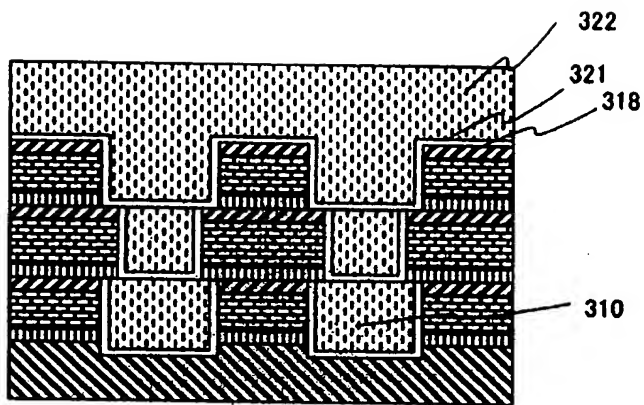


Fig. 6(a)

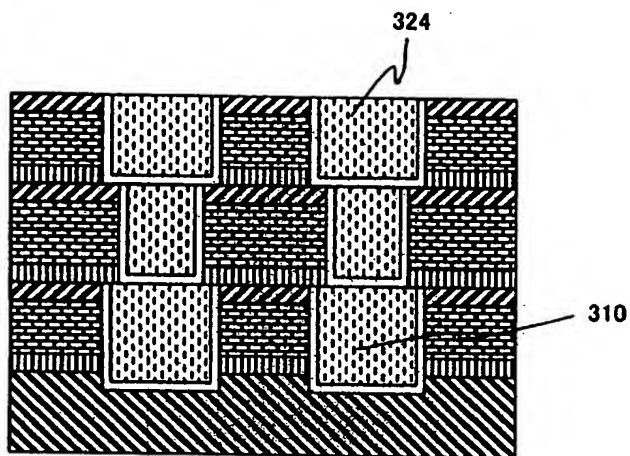


Fig. 6(b)

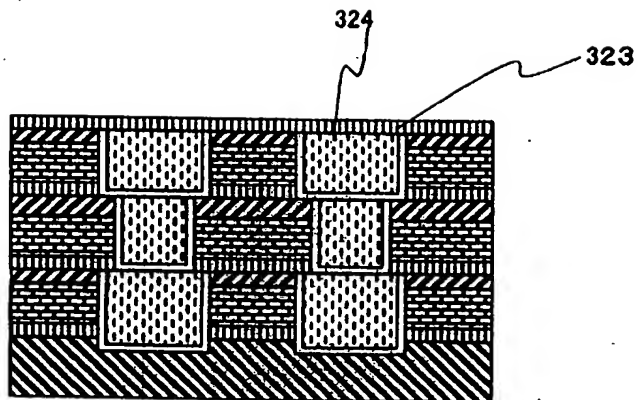
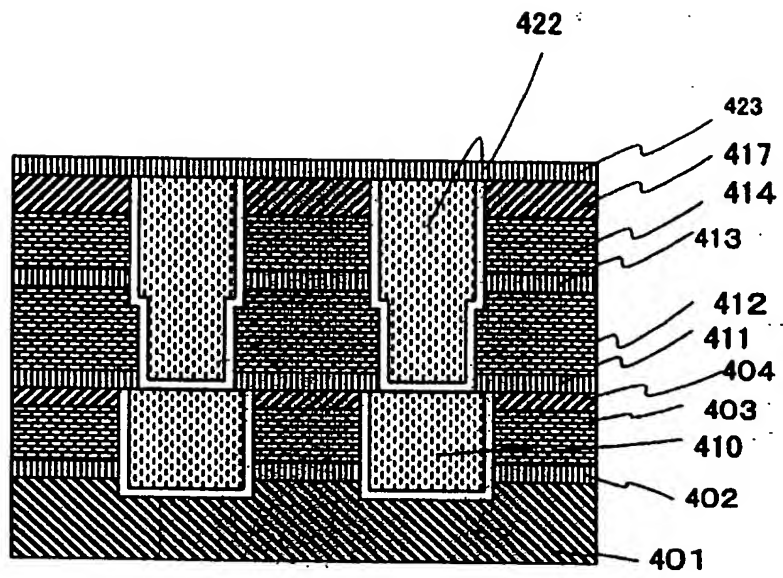


Fig. 6(c)

Fig. 7



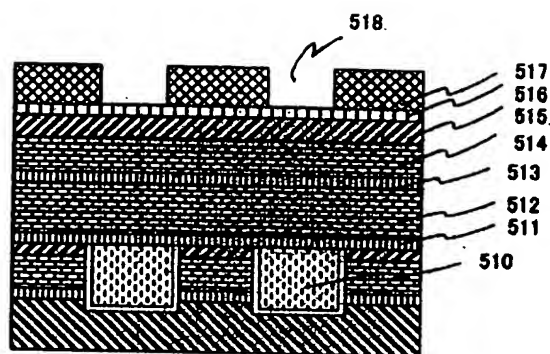


Fig. 8(a)

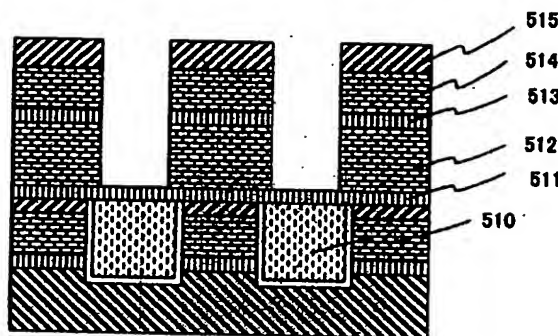


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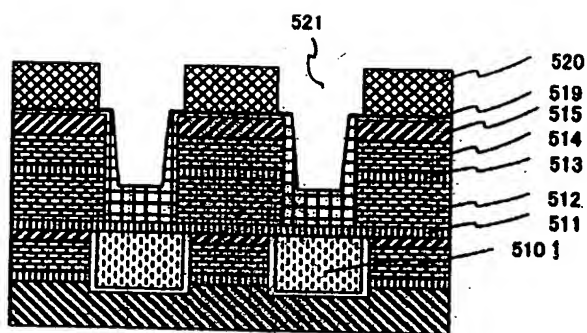


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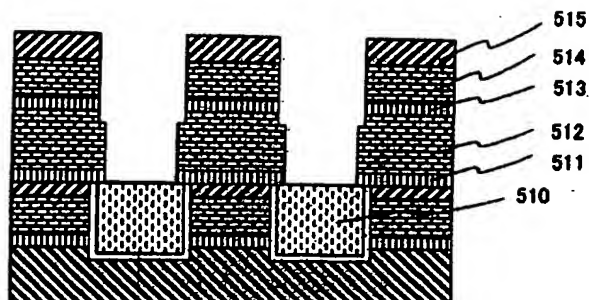


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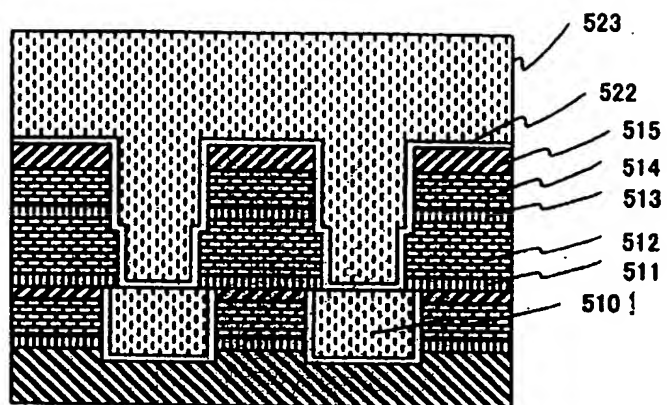


Fig. 9(a)

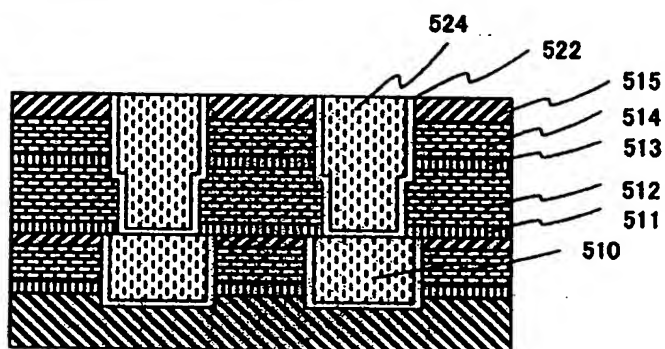


Fig. 9(b)

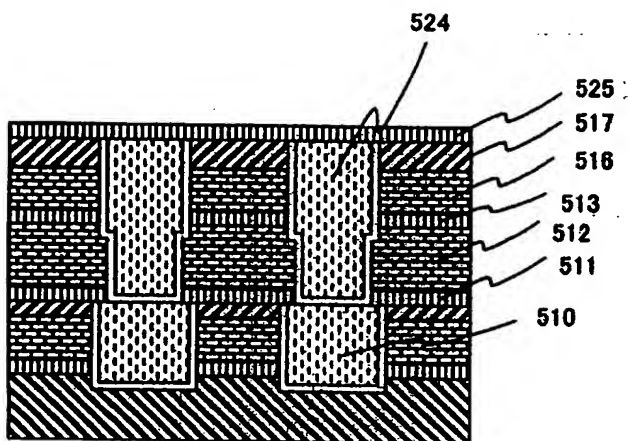


Fig. 9(c)

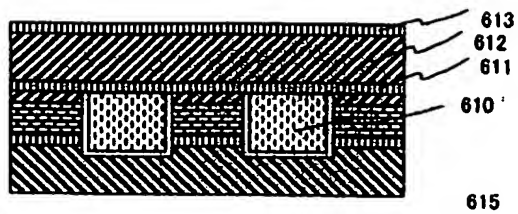


Fig. 10(a)

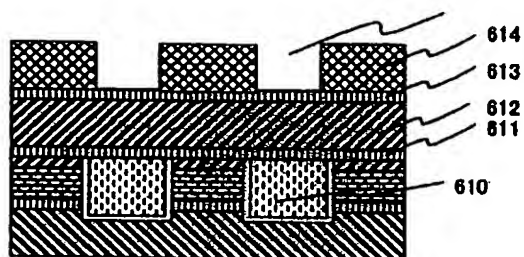


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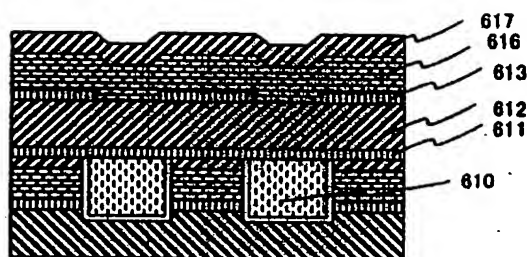


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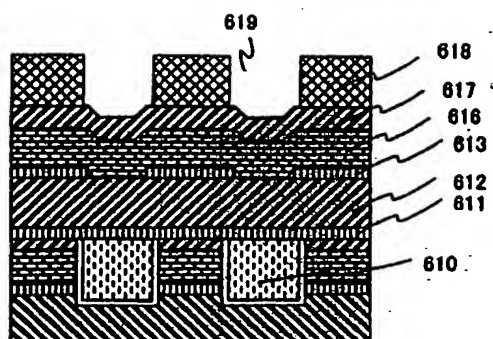


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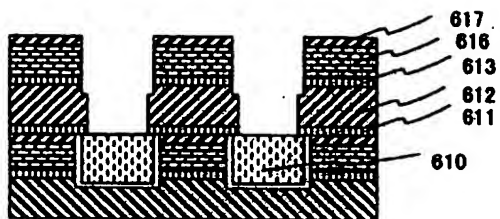


Fig. 11(a)

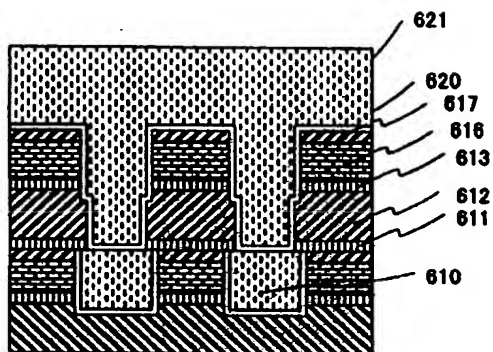


Fig. 11(b)

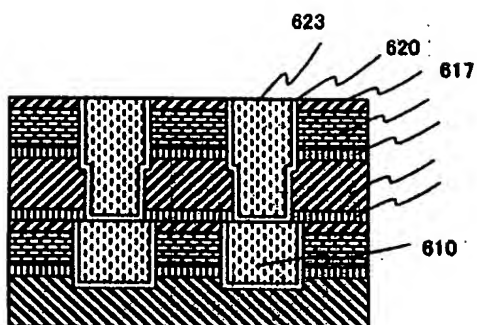


Fig. 11(c)

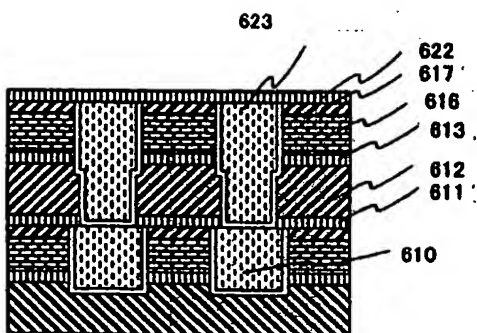


Fig. 11(d)

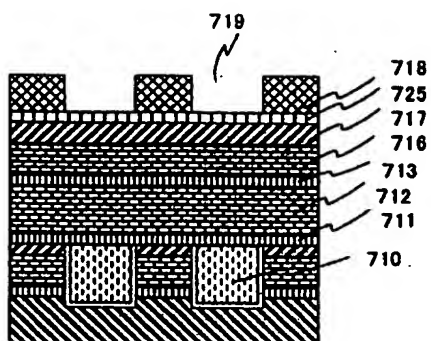


Fig. 12(a)

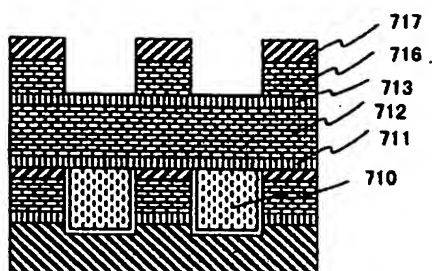


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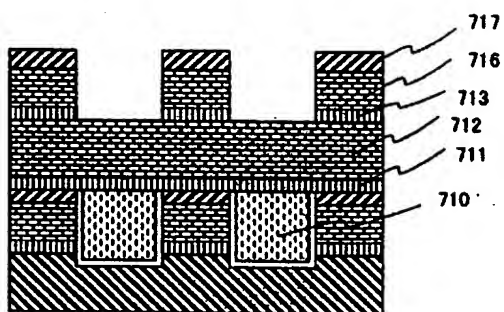


Fig. 12(c)

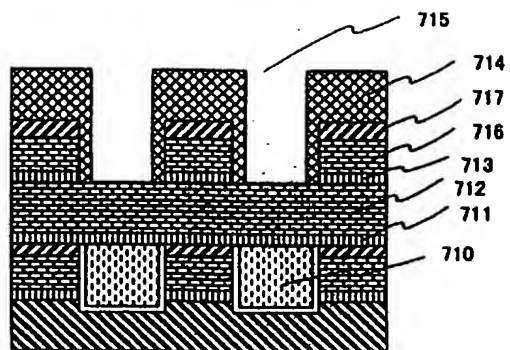


Fig. 12(d)

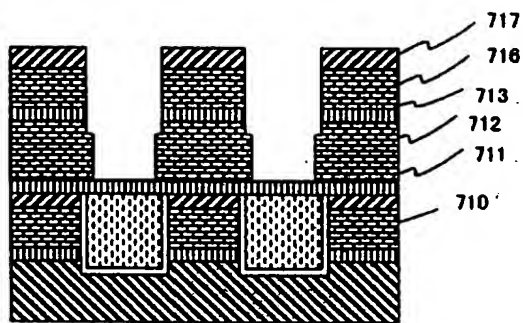


Fig. 13(a)

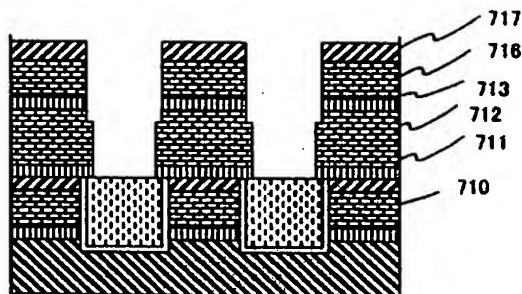


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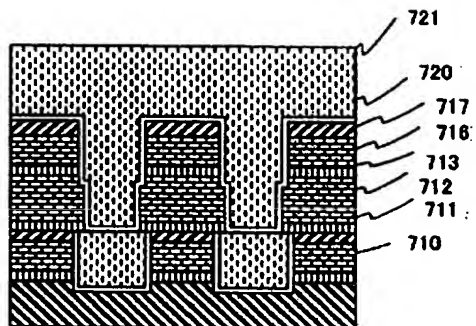


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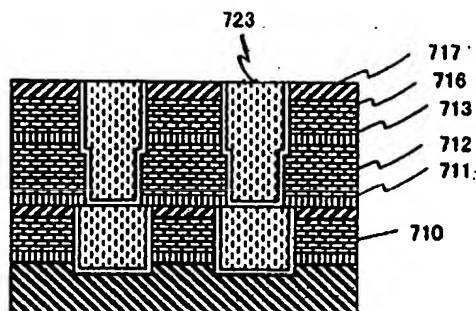
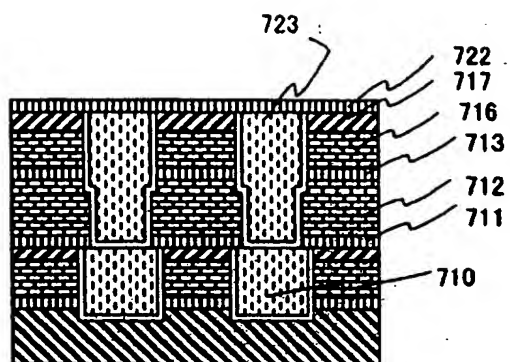


Fig. 13(d)

Fig. 14



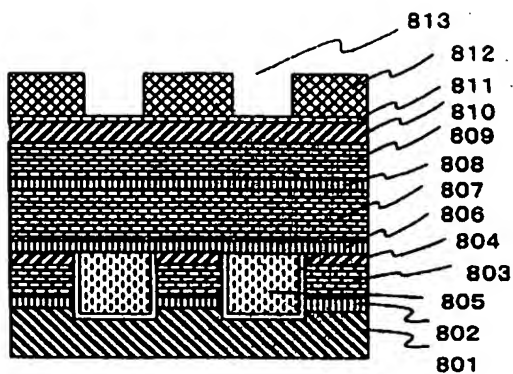


Fig. 15(a)

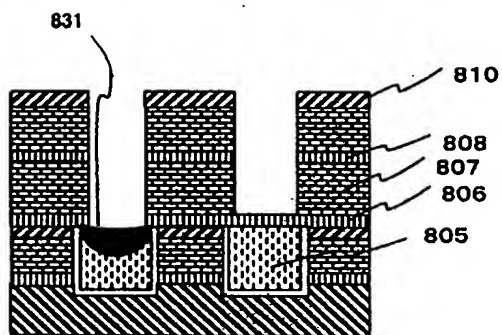


Fig. 15(b)

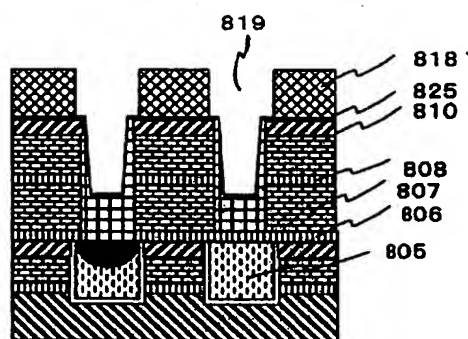


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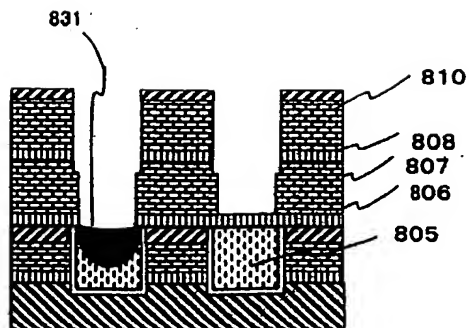


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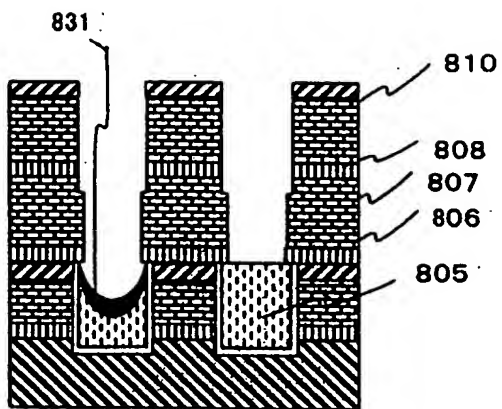


Fig. 16(a)

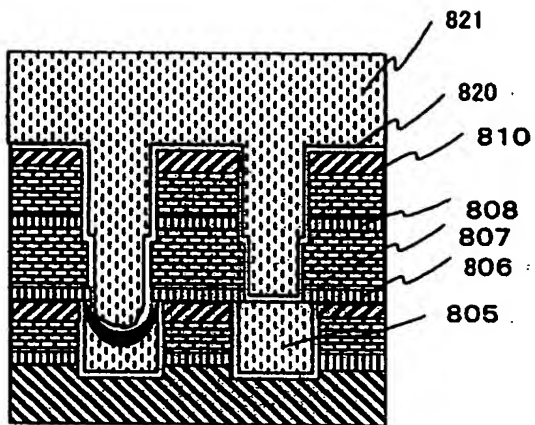


Fig. 16(b)

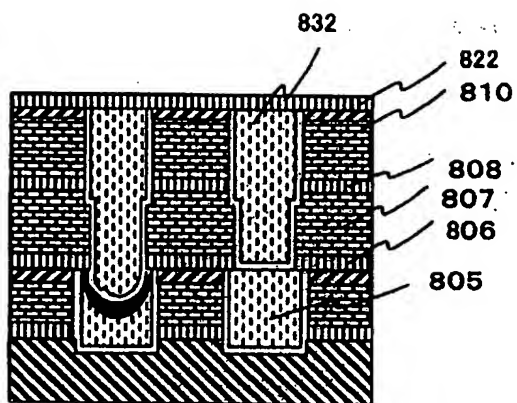
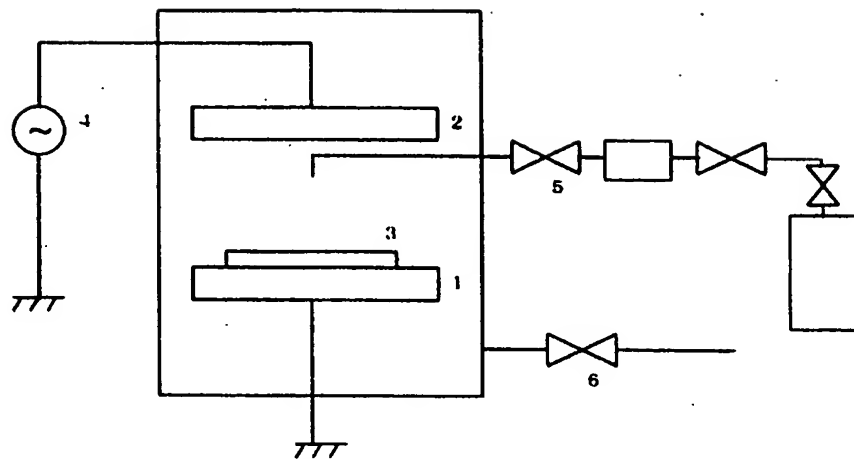


Fig. 16(c)

Fig. 17



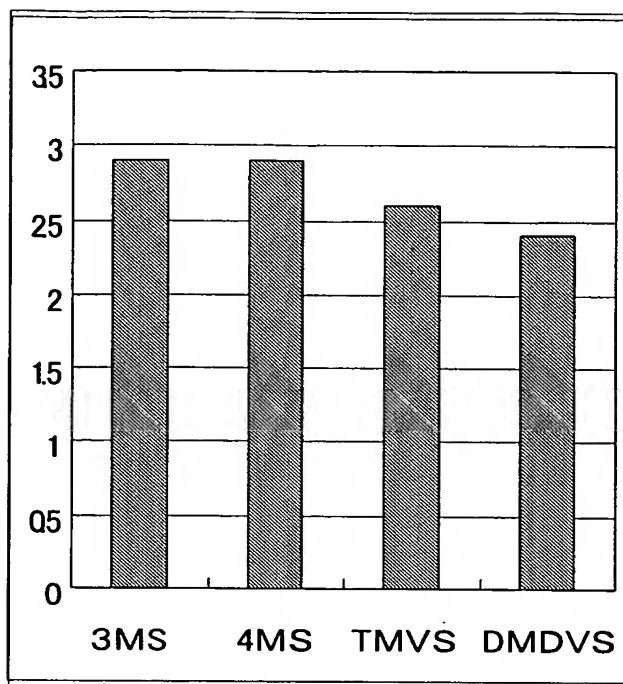


Fig.18 The dielectric constants of the SiOCH films formed with various gases.

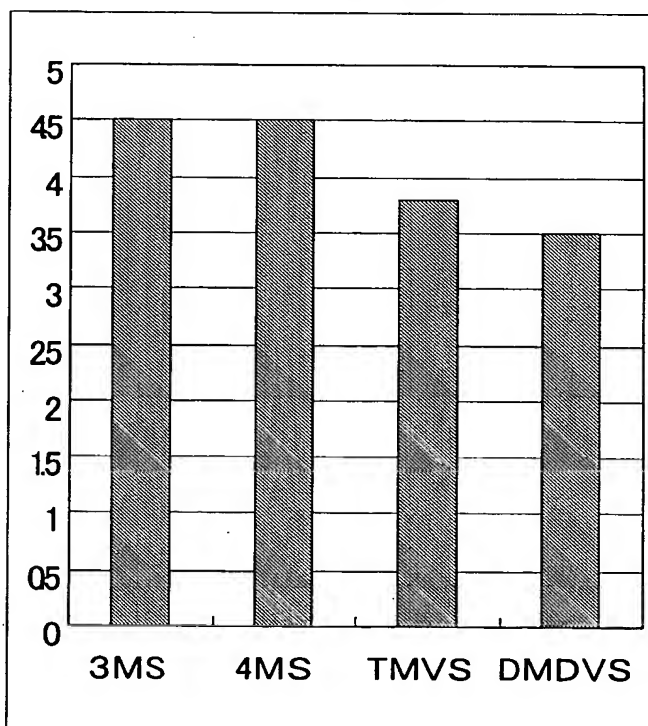


Fig.19 The dielectric constants of the SiCH films formed with various gases.

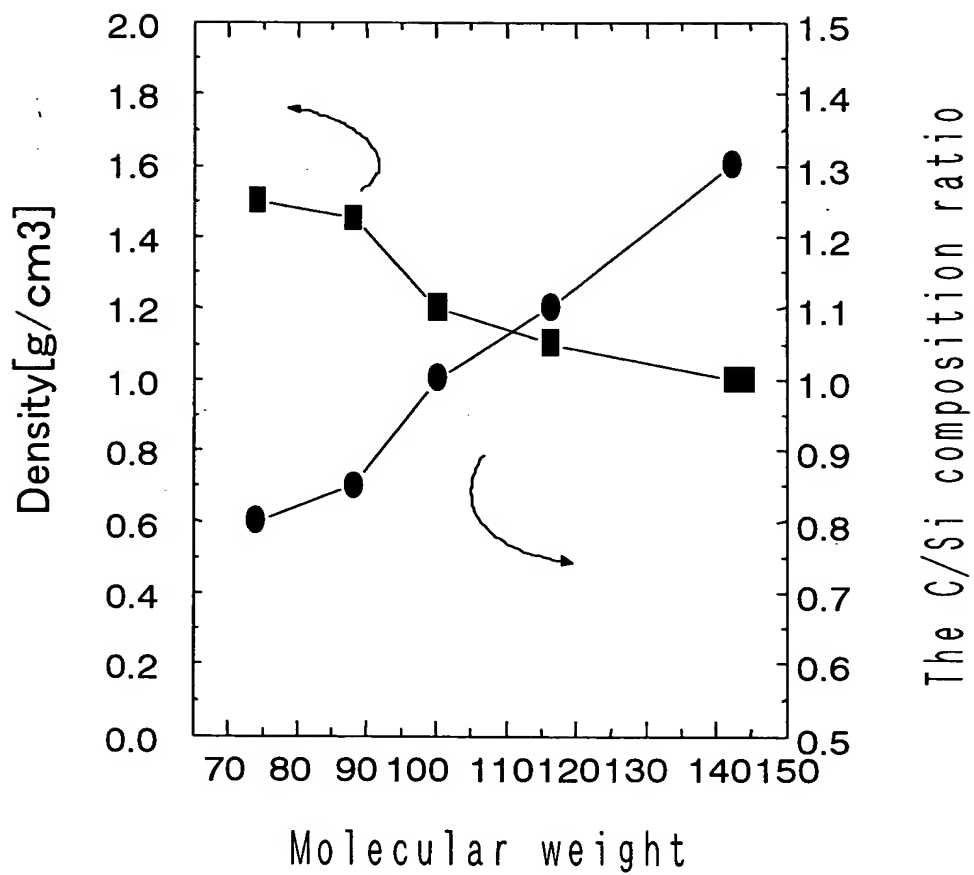


Fig. 20 The density and the composition of the SiCH film as a function of the molecular weight of the source gas.

The etching selection ratios of the SiOCH film
with respect to the SiCNH film.

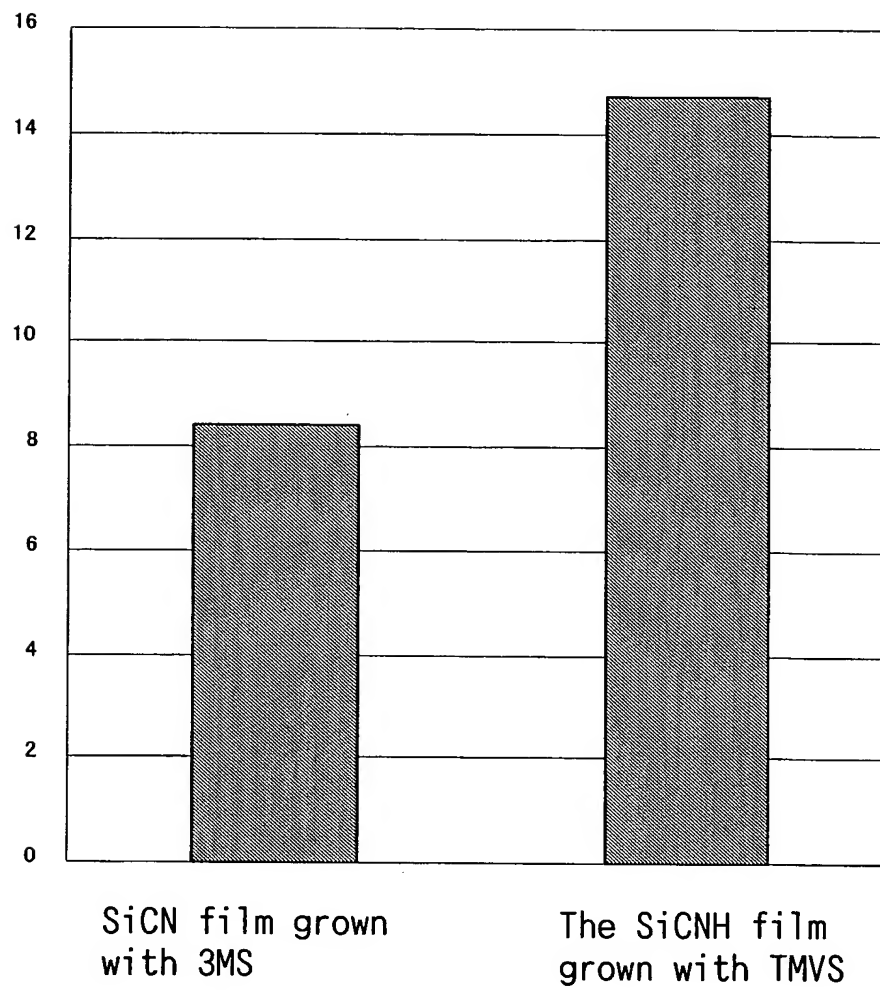


Fig. 21

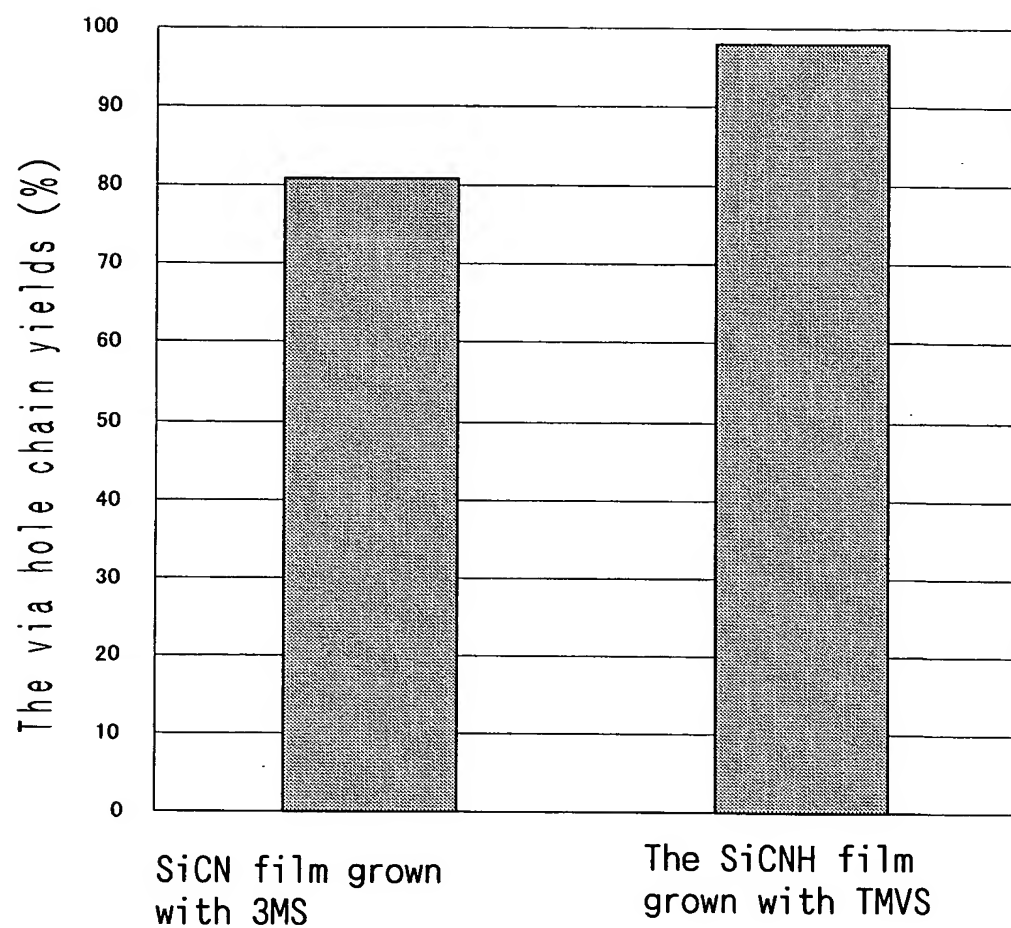


Fig. 22

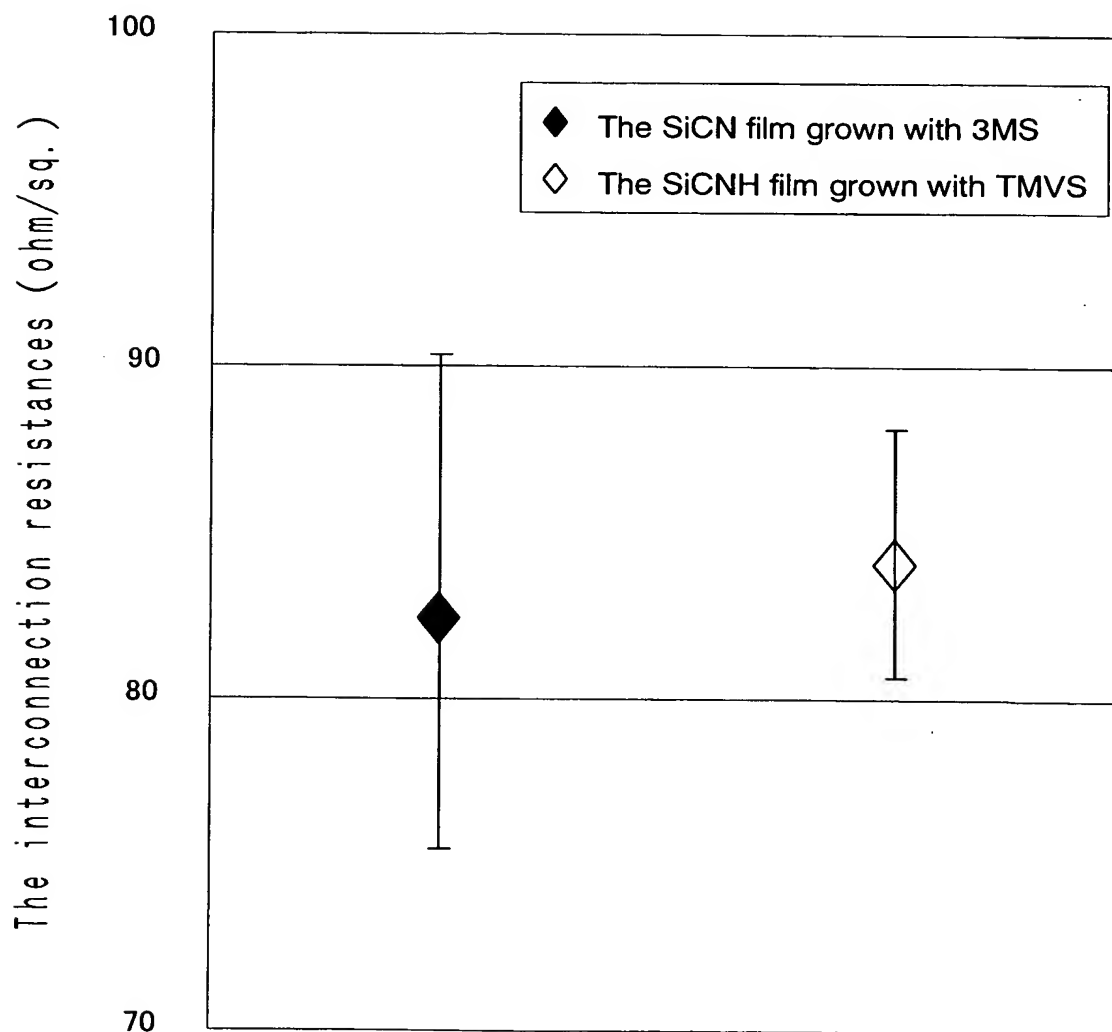


Fig. 23